

研究発表／RESULTS

Publications 2018-2017

2018

1. 松尾二郎, 濑木利夫, 青木学聰
"SIMS技術の飛躍的発展を支える新技術：新奇なイオンビーム開発から先端質量分析法まで"
表面と真空 (Vacuum and Surface Science), 2018年61巻7号, Pages 426-434, 特集「二次イオン質量分析法(SIMS)の最近の進歩と有機分析への応用」
(doi:10.1380/vss.61.426)
2. T. Prutchayawoot, H. Gnaser, R. Oki, T. Aoki, T. Seki, J. Matsuo,
"Cationization and fragmentation of molecular ions sputtered from polyethylene glycol under gas cluster bombardment: An analysis by MS and MS/MS"
International Journal of Mass Spectrometry, Volume 430, July 2018, Pages 149-157
(doi:10.1016/j.ijms.2018.05.012)
3. H.Gnaser, W.Bock, J.Matsuo,
"In situ cationization of molecular ions sputtered from organic specimens under cluster bombardment"
Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics36(3),03F106
(doi:10.1116/1.5009781)

2017

1. B.Jenčič, L.Jeromel, N.Ogrinc Potočnik, K.Vogel-Mikuš, P.Vavpetič, Z.Rupnik, K.Bučar, M.Vencelj, M.Kelemen, J.Matsuo, M.Kusakari, Z.Siketić, M.Al-Jalali, A.Shaltout, P.Pelicon,
"Molecular imaging of alkaloids in khat (*Catha edulis*) leaves with MeV-SIMS"
Nuclear Instruments and Methods in Physics Research, Section B: Beam Interactions with Materials and Atoms, Volume 404, 1 August 2017, Pages 140-145
(doi:10.1016/j.nimb.2017.01.063)
2. T.Seki, H.Yamamoto, T.Kozawa, T.Shojo, K.Koike, T.Aoki, J.Matsuo,
"Angled etching of Si by ClF₃-Ar gas cluster injection"
Japanese Journal of Applied Physics, Volume 56, Issue 6, June 2017, Article number 06HB02
(doi:10.7567/jjap.56.06hb02)
3. 松尾二郎
"「イオン化」特集号に寄せて"
Journal of the Mass Spectrometry Society of Japan, 65巻(2017)1号, P.1
(doi:10.5702/massspec.S16-59)
4. T.Seki, H.Yamamoto, T.Kozawa, K.Koike, T.Aoki, J.Matsuo,
"Fabrication of a Si lever structure made by double-angled etching with reactive gas cluster injection"
Applied Physics Letters, Volume 110, Issue 18, 1 May 2017, Article number 182105
(doi:10.1063/1.4982970)